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PATENT 10/591476

033082M343

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Yasuhiko KOJIMA, et al.

International Application No.: PCT/JP2005/003155

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U.S. Serial No.: To Be Assigned

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INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to the duty of disclosure under 37 C.F.R. 1.56, Applicants are enclosing an Information Disclosure Citation Form (PTO-1449) which lists the documents noted in the International Search Report (ISR) filed herewith.

It is respectfully requested that the cited documents be considered by the Examiner in the above-identified patent application and that the cited documents be made officially of record therein. It is further requested that a listing of the same appear on the face of any patent which may issue from this application.

Respectfully submitted,  
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FORM PTO-1449  INFORMATION DISCLOSURE STATEMENT	ATTY. DOCKET 033082M343	SERIAL NO. To Be Assigned <b>10/591476</b>
	APPLICANT: Yasuhiko KOJIMA, et al.	
	FILING DATE Herewith	GROUP ART UNIT To Be Assigned

## U.S. PATENT DOCUMENTS

*Examiner's Initials		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE, IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						

## FOREIGN PATENT DOCUMENTS

*Examiner's Initials		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION YES NO	
	AH	63-5424	2/3/88	Japan			Abstract	
	AI	2003-193233	7/9/03	Japan			Abstract	
	AJ							
	AK							
	AL							
	AM							
	AN							
	AO							
	AP							

## OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

AQ	Per Martensson et al., "Growth and Selectivity in the Cu(II) – 2,2,6,6-tetramethyl-3,5-heptanedionate/H <sub>2</sub> Process", Journal of the Electrochemical Society, 1998, Vol. 145, No. 8, pp. 2926-2931
AR	Mikko Utriainen, et al., "Studies of metallic thin film growth in an atomic layer epitaxy reactor using M(acac) <sub>2</sub> (M=Ni, Cu, Pt) precursors, Applied Surface Science, 2000, vol. 157, pp. 151-158
AS	

EXAMINER:	DATE CONSIDERED:
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>	